

Beam Expander 1x-8x | 515-540 nm

High Power Systems



- Diffraction-limited performance for all magnifications
- No internal foci & no internal reflections in elements for all magnifications
- Highest beam pointing stability (≤ 0.3 mrad)

	515-540 nm
GDD ¹⁾ :	1580 fs ²
LIDT coating pulsed; CW ²⁾ :	2.5 J/cm ² * (τ [ns]) ^ 0.30; 2.5 MW/cm ²
LIDT system pulsed; CW ²⁾ :	0.20 J/cm ² * (τ [ns]) ^ 0.30; 0.20 MW/cm ²

Magnification	\varnothing entrance pupil ³⁾ 515-540 nm	Expansion scale	Focusing scale
1x	9.0 mm	10.3 mm	0.0 mm
2x	9.0 mm	17.5 mm	11.4 mm
3x	9.0 mm	17.0 mm	15.2 mm
4x	7.5 mm	14.6 mm	17.0 mm
5x	6.0 mm	11.4 mm	18.2 mm
6x	5.0 mm	7.8 mm	18.9 mm
7x	4.5 mm	4.0 mm	19.5 mm
8x	4.0 mm	0.0 mm	19.9 mm

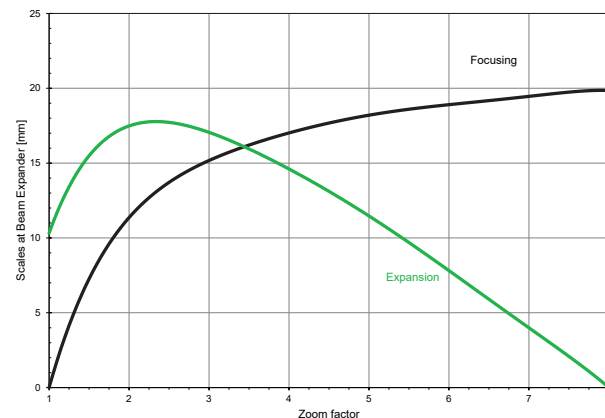
Order Number: 627443

¹⁾ Group delay dispersion | ²⁾ See technical note
³⁾ Recommended maximum diameter of entrance pupil
⁴⁾ For UV lasers, the LIDT values are valid for pulse durations > 10 ps.
 For shorter pulses please be advised to test.

Specification

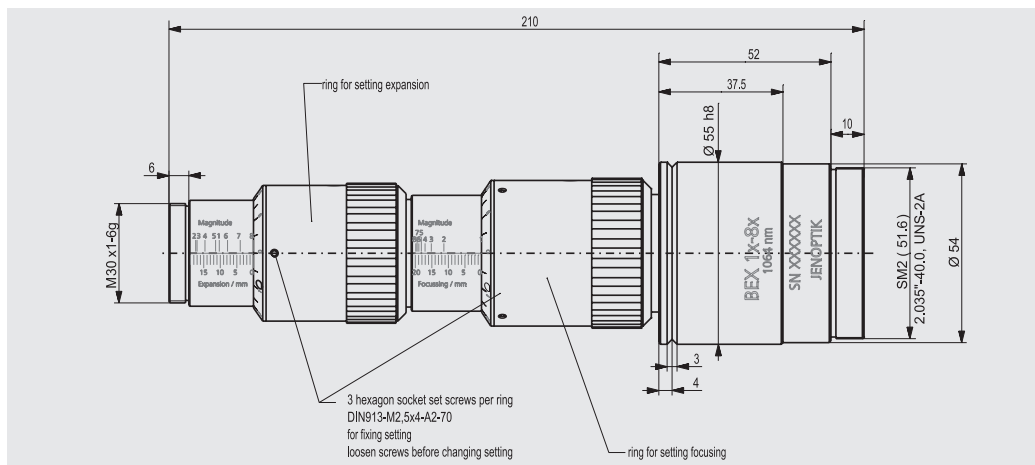
Materials

Entrance elements:	Fused silica
Exit elements:	Fused silica
Transmission:	≥ 97 %
Beam pointing stability:	≤ 0.3 mrad
Mounting \varnothing :	55.0 (+0.0/-0.05) mm or mounting threads M30x1
Weight:	0.54 kg



This graph shows an exemplary configuration.

Fine adjustment of the zooming and focusing scale by the combination of mm scales and vernier scales.



Registered Design in
 DE 40 2016 001 282.4
 Registered in CN, EU,
 HK, IN, JP, KR
 Pending in TW
 Granted Patent
 DE 10 2015 009 124
 Patent pending CN-,
 CZ-, KR-, US-Appl.

Same dimensions for
 all wavelength versions.